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- Authors and coauthors attending the meeting must obtain funding for their registration fees, travel, and accommodations, independent of SPIE, through their sponsoring organizations before submitting abstracts.
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- SPIE is authorized to circulate your abstract to conference committee members for review and selection purposes.
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- Please also submit a 100-word abstract suitable for early release. If accepted, this abstract text will be published prior to the meeting in online or printed programs promoting the conference.
- A full-length manuscript (8-12 pages) for any accepted oral or poster presentation (including keynote, invited, and solicited presentations) will be submitted for publication in the SPIE Digital Library, printed conference Proceedings, and CD-ROM.

### 2. Prepare to submit:

- Have all contact information (full names, affiliations, addresses, phone numbers, and emails) for your coauthors ready.
- Only original material should be submitted.
- Abstracts should contain enough detail to clearly convey the approach and the results of the research.
- Optional Additional Supplemental File: This file must contain your 500-word abstract text, at least one figure, and must be submitted in Microsoft Word or PostScript format. Supplemental files are strongly encouraged as they provide additional explanation and clarity for the organizing committee during the abstract review process.
- Commercial papers, papers with no new research/development content, and papers where supporting data or a technical description cannot be given for proprietary reasons should not be submitted, and will not be accepted for presentation in this conference.

### 3. Submit your abstract online:

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**Abstract Due Date:  
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**Manuscript Due Date:  
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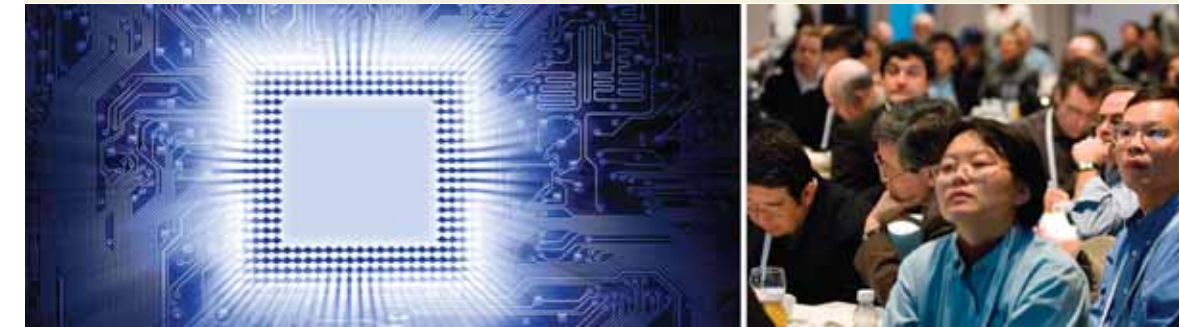
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### Topics include:

- ▶ Emerging Lithographic Technology and Nanofabrication
- ▶ Optical Microlithography
- ▶ Advances in Resist Material and Processing
- ▶ Metrology, Inspection, and Process Control
- ▶ LCD Application

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# SPIE Lithography Asia Taiwan

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## Please join us in Taipei for this exciting international forum!

It is our great pleasure to invite you to attend the second SPIE Lithography Asia conference, featuring presentations from leading researchers, developers, and innovators, and building on last year's very successful conference. This is your opportunity to present your research and connect with others working at the leading edge of semiconductor device and flat panel display (FPD) technologies.

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## SPIE Lithography Asia—Taiwan

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The semiconductor and FPD industries have expanded globally for several decades, and now a major portion of microelectronics and FPD products are manufactured in Asia. This has brought an increasing segment of R&D for lithography processes and equipment technology to Asia as well. Furthermore, the pace of innovation and development has progressively accelerated in recent years. This conference is intended to stimulate a face-to-face exchange of the latest developments of microlithography techniques used in the current and future electronics manufacturing process.

Please submit your abstracts on one or more of the following topics:

### Emerging Lithographic Technology and Nanofabrication

- Optical lithography extension (shorter than 157 nm)
- EUV lithography
- E- and ion- beam technology
- Nano-imprint lithography
- Application on nanostructures

### Optical Microlithography

- ArF immersion lithography
- RET technology
- Double exposure/double patterning lithography
- OPC modeling
- Photo cluster automation

### Advances in Resist Material and Processing

- Emerging resist materials
- Advancement in immersion resists
- Resist process optimizations
- Resist material for LCD application
- Double exposure material

### Metrology, Inspection, and Process Control

- Advancement in CD metrology
- Advancement in overlay metrology
- Advancement in defect inspection
- Process control for CD and overlay
- Emerging metrology technology

### LCD Application

- Imaging technology
- Process control
- Material technology
- Automation and productivity

## General Information

### Venue

Sheraton Taipei Hotel  
12 Chung Hsiao East Road Section 1  
Taipei 100, Taiwan

SPIE Lithography Asia - Taiwan will be located in the Sheraton Taipei Hotel. The hotel provides five-star facilities and exquisite services with over twenty years of experience, and is located in the center of Taipei's commercial, business and transportation areas, with easy access to the Mass Rapid Transit stop adjacent to the hotel and close to Hsimen, Taipei Main Station, east Taipei, movie theaters, and Song Shan Domestic Airport.

Complete information about hotel reservations, travel to Taiwan, hotel accommodations, and other details will be available in the Advance Program and at [www.spie.org](http://www.spie.org) in July 2009. Opening of the hotel reservation process is scheduled for approximately July 2009. SPIE will arrange special discounted hotel rates for SPIE attendees. See [www.spie.org/litho-asia-call](http://www.spie.org/litho-asia-call) for the latest information.

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Taipei Skyscraper

### About Taipei

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